

The 1st Plasma Materials Science Hall of Fame Prize

was awarded to

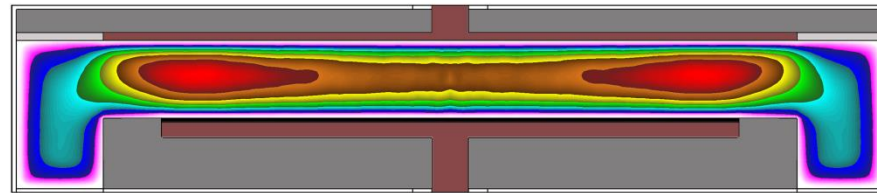
Prof. Mark J. Kushner,

The University of Michigan,

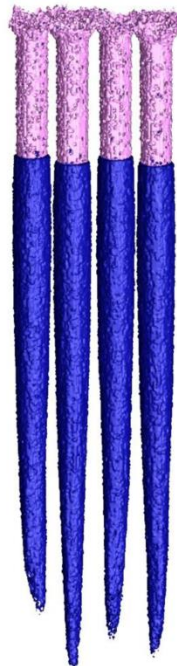
for the excellent achievements in plasma simulations for material processes and practical applications for microelectronics.



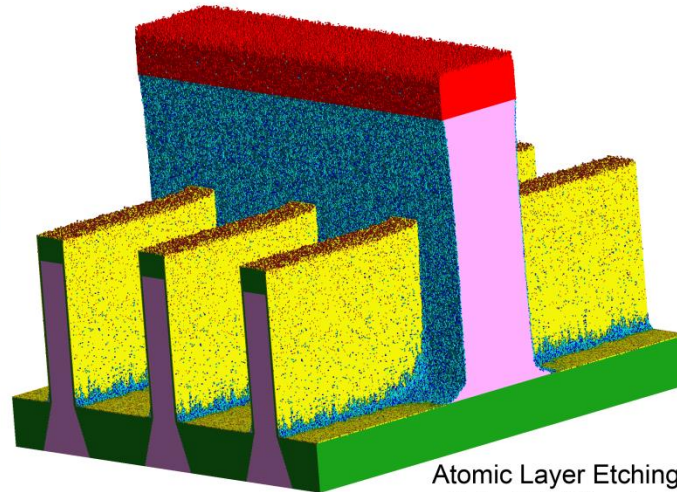
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Dual Frequency Capacitively Coupled Plasma
For Etching Semiconductor Materials



Twisting of High Aspect Ratio Vias
Etched in SiO₂



Atomic Layer Etching
of Fin-FET Structure

Reactor-to-feature scale simulation tools have improved fundamental understanding and provided design capabilities to industry.